

October 21 (Wed.), 2026

[Oral 07] Post-CMP Cleaning / Defect Engineering

11:25-12:50

International Conference Hall (B1F)

● Session Chair: Jingoo Park (Hanyang Univ., Korea)

11:25-11:50 **[Invited]** Qnity Cu PCMP Technology Evolution from Mature to Advanced

[Oral 07-1] [Node](#)

[Ping Hsu](#) (Qnity, Taiwan)

11:50-12:10 [Comparative Evaluation of Ammonium- and QAC-Based Alkaline Cleaning](#)
★[Oral 07-2] [Chemistries for Molybdenum Post-CMP Cleaning](#)

[Gyeongwon Lee](#), Palwasha Jalalzai (Hanyang Univ., Korea), Junsang Lee, Gayoung Kim, In-Kwon Kim, Sangkyun Kim (Samsung Electronics Co., Ltd., Korea), Tae-Gon Kim, Jihoon Seo, and Jin-Goo Park (Hanyang Univ., Korea)

12:10-12:30 [Additive-Free Post-CMP Cleaning for Fine Ceria Particle Removal with Gas-](#)
★[Oral 07-3] [Dissolved Water](#)

[Hyeonjeong Lee](#), Donghwan Choi, Jinhyoung Lee, Yechan Kim, and Taesung Kim (Sungkyunkwan Univ., Korea)

12:30-12:50 [Effect of pH on Acoustic Bubble Dynamics, Particle Removal Efficiency, and](#)
★[Oral 07-4] [Pattern Damage During Megasonic Cleaning](#)

[Mir Jalal Khan](#) (Hanyang Univ., Korea), Yunhee Cho, Wonseob Cho (BASF, Korea), Andreas Klipp (BASF SE, Germany), Jihoon Seo, and Jin-Goo Park (Hanyang Univ., Korea)